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DETAILED ACTION

Allowable Subject Matter

- 1. Claims 1-19 are allowed.
- 2. The following is an examiner's statement of reasons for allowance:

Regarding independent claims 1 and 11, the prior art fails to disclose or make obvious a polarity exchanger or an ion implanter that comprises a polarity exchanger wherein said polarity exchanger comprises a stripping canal, a gas supply unit with a gas circulation unit for providing a stripping gas into the stripping canal a flow meter for measuring a flow rate of the stripping, an ammeter for measuring a driving current applied to the gas circulation unit and a monitoring unit for generating a control signal to control a process for changing the polarity of the ion beam in accordance with a measured flow rate of the stripping gas and a measured driving current.

Claims 2-10 and 12-19 are allowed by virtue of their dependency on claims 1 and 11 respectively.

The main feature that separates the apparatus apart from prior art is the use of a flow meter to measure the gas flow rate and a current meter to measure the driving current of the circulation unit. The prior art has used a fixed pumping speed and controlled gas flow in the stripper by using a fixes orifice and controlling the pressure of the gas feeding the orifice and a vacuum sensor to monitor the pressure in the stripping chamber.

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3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance"

Relevant Prior Art

3. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Kwon (USPN 6639230) uses a current sensor for checking for abnormal conditions and a controller to turn off a turbo pump.

Mack et al. (USPN 5959305) use a mass flow controller (MFC) to regulate gas flow to a vacuum chamber. Gas may be supplied to arc chamber at any suitable flow rate.

Choi et al. (USPN 6462331) uses a current detector to detect a current flowing to a turbo pump and a controller stops the pump and the ion implantation apparatus if the current is out of a specified range.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to James J. Leybourne whose telephone

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number is (571) 272-2478. The examiner can normally be reached on M-F 9:00-6:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John R Lee can be reached on (571) 272-2477. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

October 19, 2004

JJL

SUPERVISORY PATENT EXAMINER